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(12) **United States Design Patent**  
**Chen**

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(54) **MASK**

(76) **Inventor:** **Chun-Nan Chen**, 182, Haichung St.,  
An Nan District, Tainan (TW)

(\*\*) **Term:** **14 Years**

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(51) **LOC (8) Cl.** ..... **29-02**

(52) **U.S. Cl.** ..... **D29/108**

(58) **Field of Classification Search** ..... D29/102-110,  
D29/122; 2/5, 6.1, 6.3, 6.5-6.7, 411, 414,  
2/423-425, 431, 8-9, 427; 128/201.24, 206.21,  
128/206.28; D24/110.1, 110.2, 110.3  
See application file for complete search history.

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*Primary Examiner*—Ruth McInroy

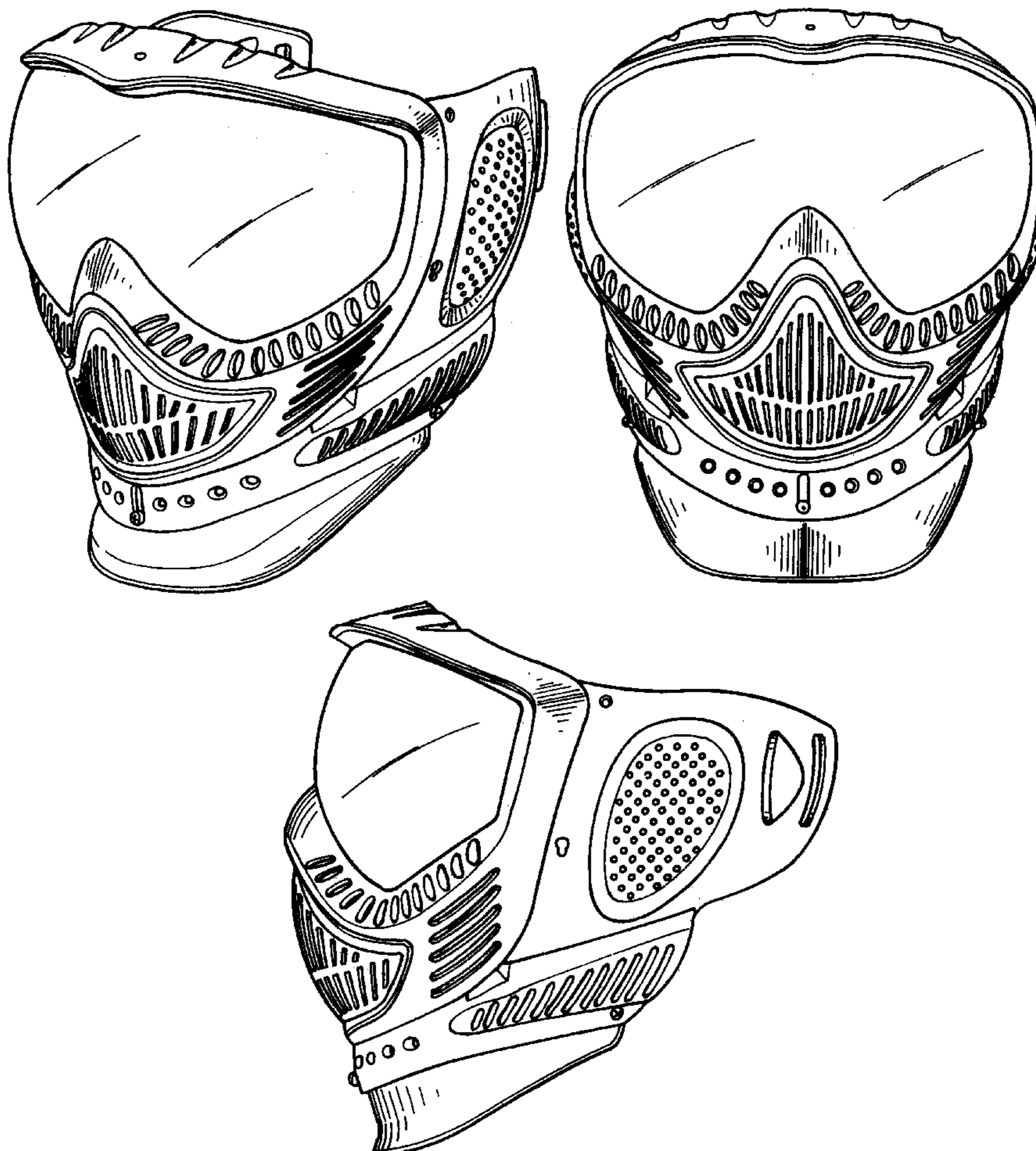
(57) **CLAIM**

The ornamental design for a mask, as shown and described.

**DESCRIPTION**

FIG. 1 is a perspective view of a mask showing my new design;  
FIG. 2 is a front elevational view thereof;  
FIG. 3 is a rear elevational view thereof;  
FIG. 4 is a left side elevational view thereof;  
FIG. 5 is a right side elevational view thereof;  
FIG. 6 is a top plan view thereof; and,  
FIG. 7 is a bottom plan view thereof.

**1 Claim, 4 Drawing Sheets**



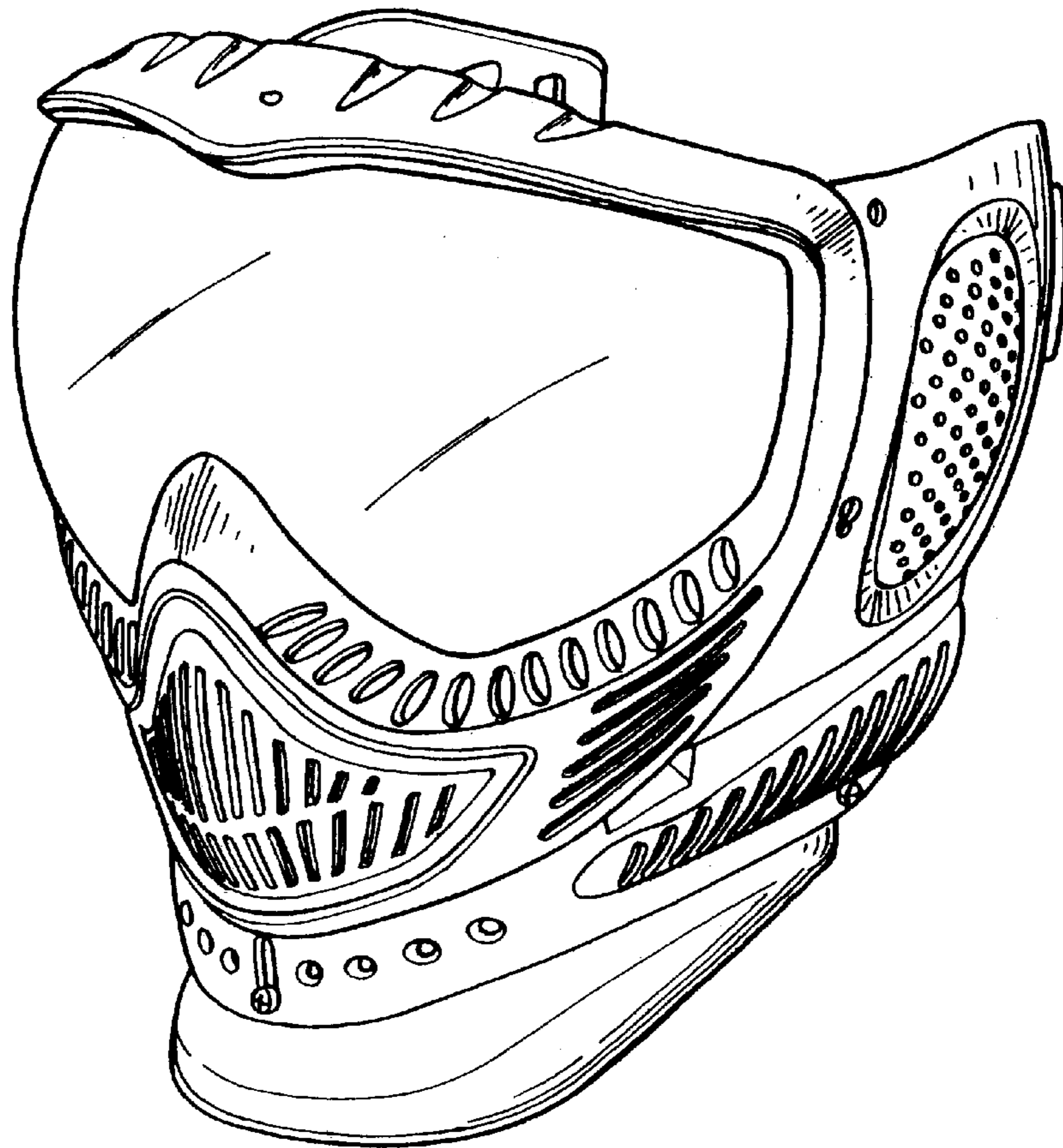


FIG.1

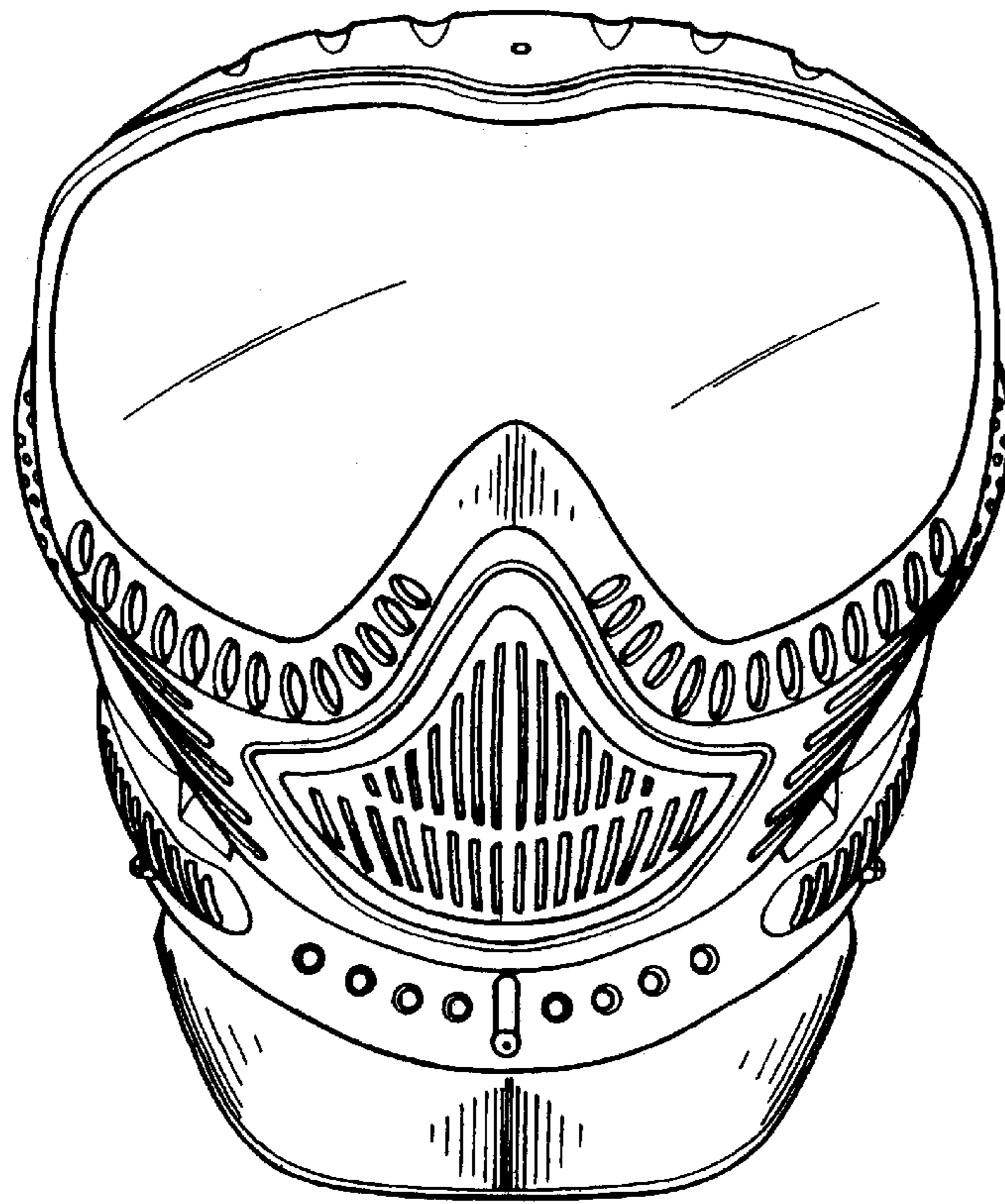


FIG. 2



FIG. 3



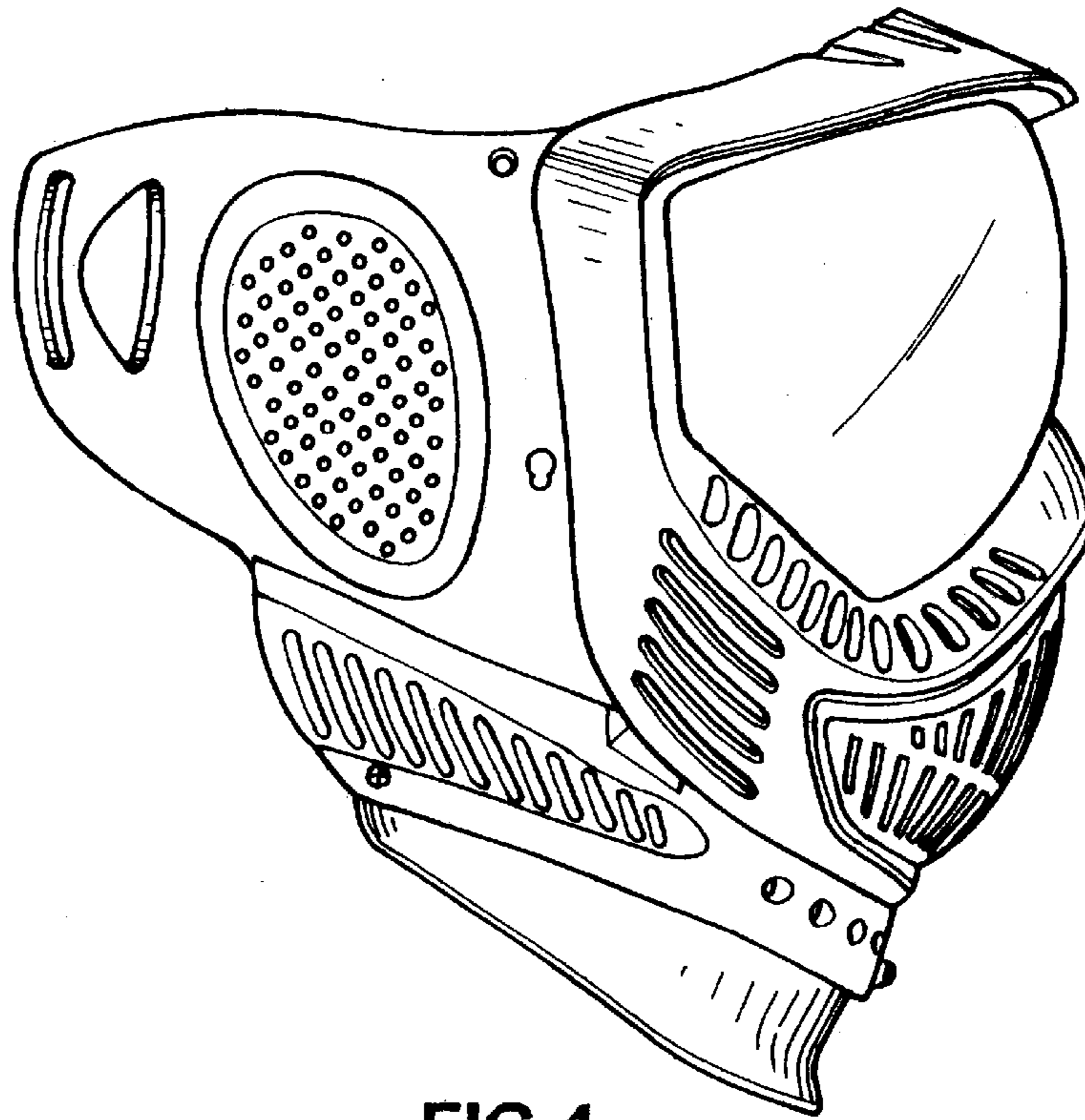


FIG. 4

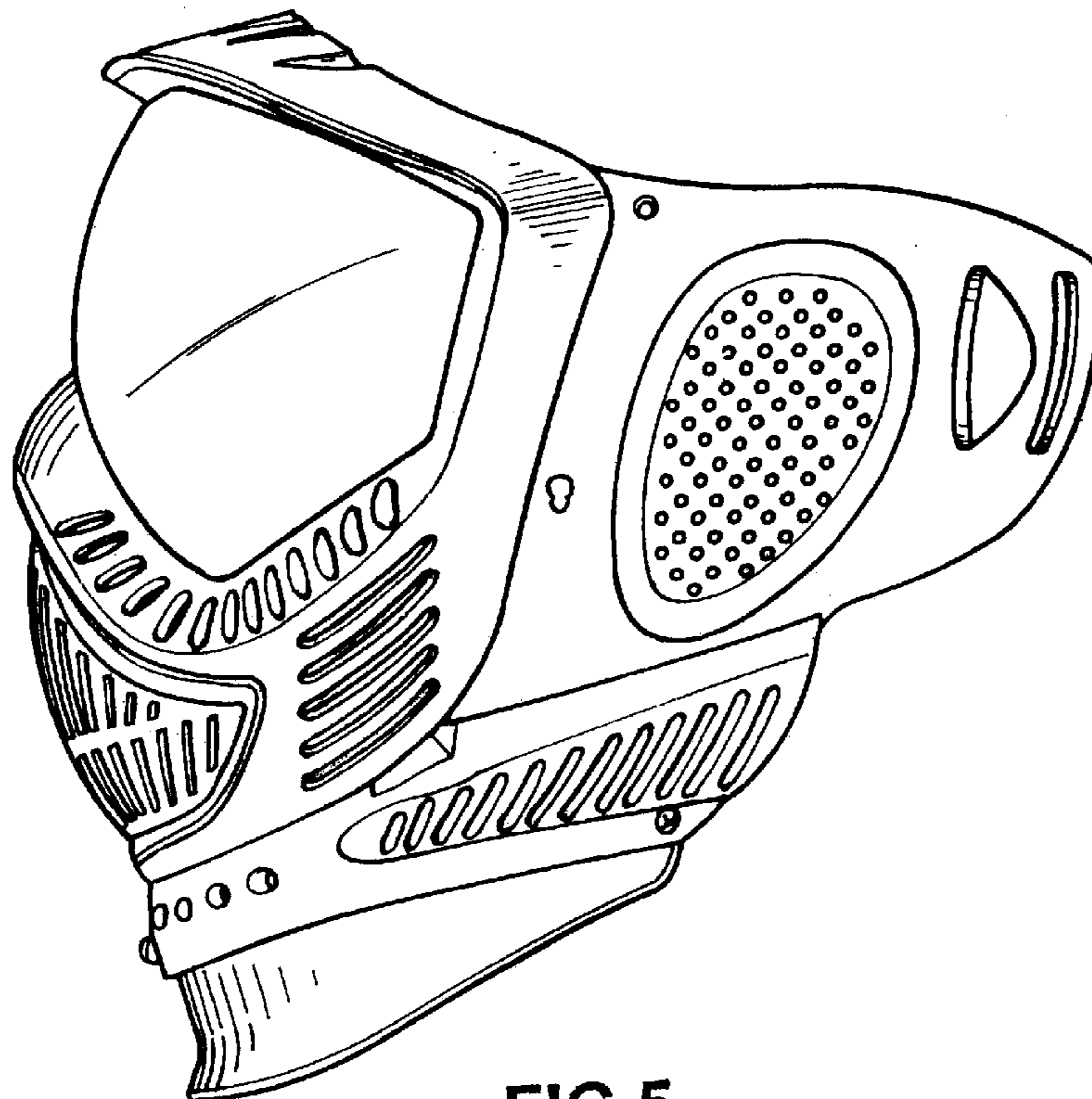


FIG. 5

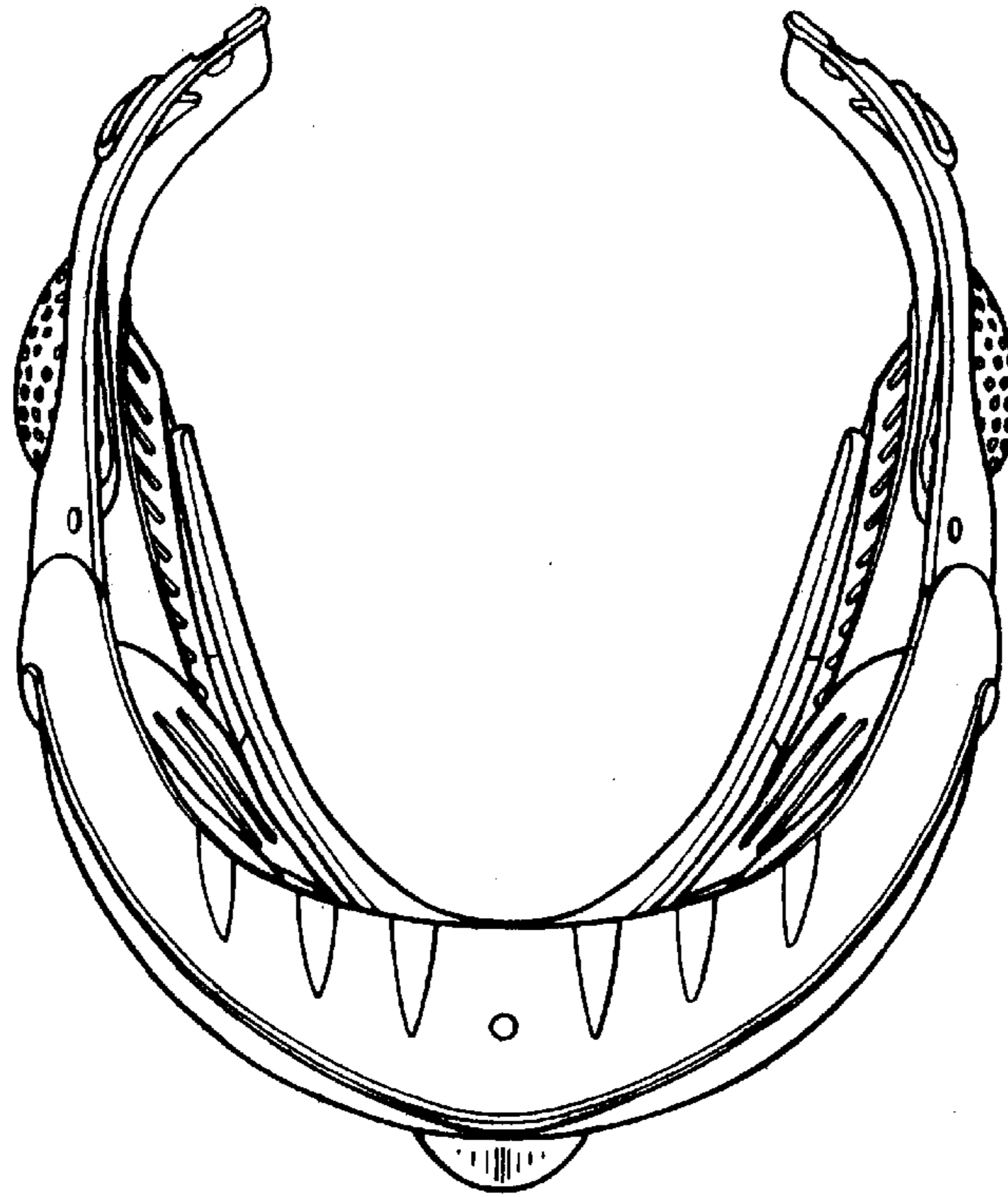


FIG. 6

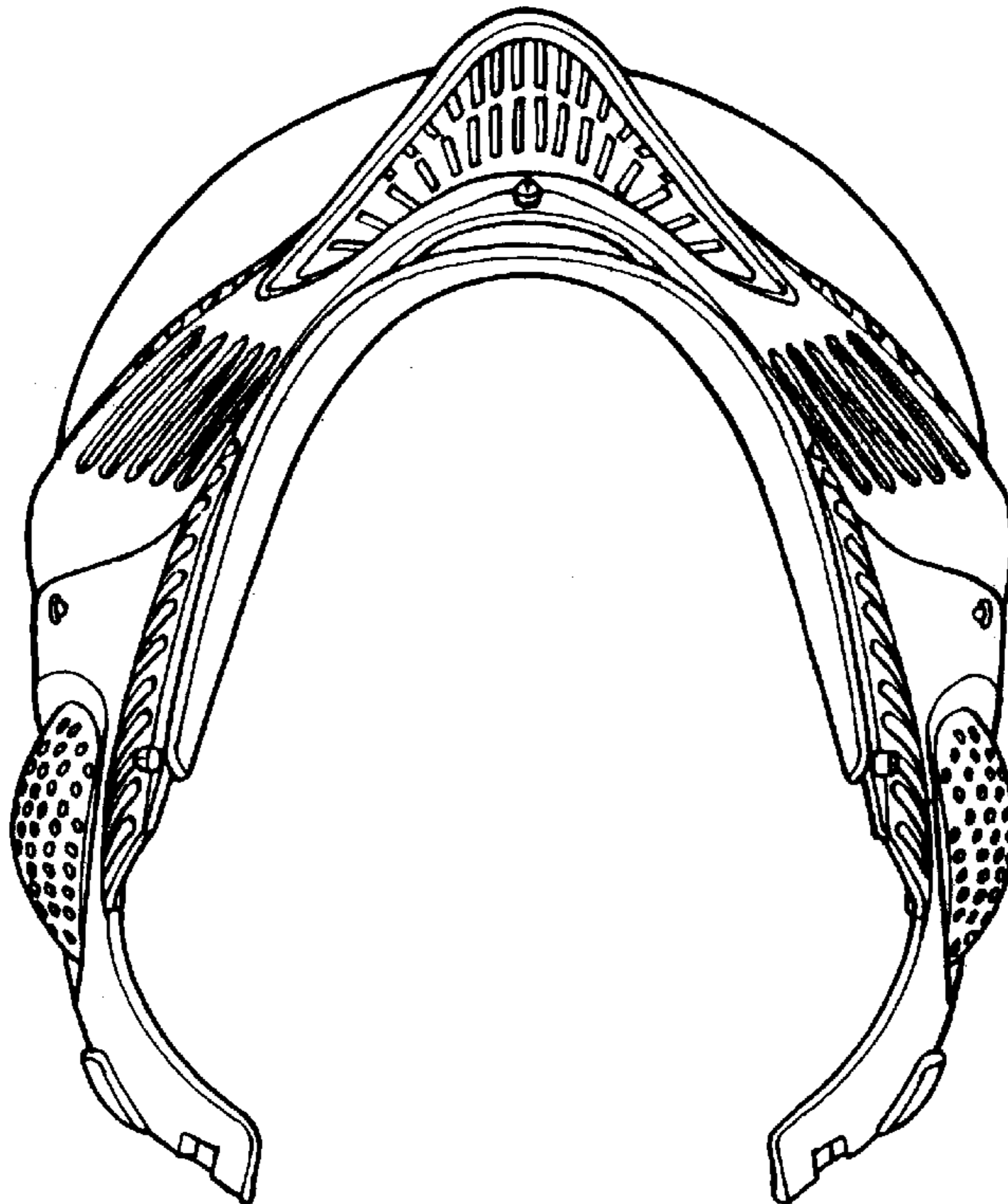


FIG. 7